Photolithography

![Chemical structure diagram with labels for spinning process and coated wafer]

W. S. Finko, *Microwave Processing*, Fig. 3-11, p. 430 (McGraw-Hill, New York, 1967)

![Graph showing photoresist thickness vs. distance from edge]

Dispense speed 500, 500, 6000
Spin speed 3000, 6000

Photoresist on 3-in bare silicon slice